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YS

**NONFERROUS METALS INDUSTRY STANDARD OF THE
PEOPLE'S REPUBLIC OF CHINA**

YS/T 935-2013

**Standard guide for analysis and reporting the impurity content
and grade of high purity metallic sputtering targets for
electronic thin film applications**

电子薄膜用高纯金属溅射靶材纯度等级及杂质含量分析和报告标准指南

(English Translation)

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What this standard covers

This standard specifies the electronic thin films with high purity metal sputtering target purity levels defined method, impurity content analysis methods, sampling target purity level reporting rules and standards and so on. This standard applies to all

Document data

International classification (ICS): 77.150.99.

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Adopted international standard: ASTM F2113-01(2011), NEQ.

Standards quoted by this document

GB/T 14265; GB/T 29658; YS/T 871; YS/T 922; GB/T 20975.1; GB/T 20975.2; GB/T 20975.3; GB/T 20975.4; GB/T 20975.5; GB/T 20975.6; GB/T 20975.7; GB/T 20975.8; GB/T 20975.9; GB/T 20975.10; GB/T 20975.11; GB/T 20975.12; GB/T 20975.13; GB/T 20975.14; GB/T 20975